

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/813,543
Filing Date March 30, 2004
Confirmation No. 8087
Inventor Gealy, F. Daniel
Assignee Micron Technology, Inc.
Group Art Unit 1792
Examiner Keath T. Chen
Attorney's Docket No. MI22-3685
Title: Method for Reducing Physisorption During Atomic Layer Deposition

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References - - See attached Form PTO/SB/08a

The attached Form PTO/SB/08a is submitted in compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, and your attention is directed to the reference listed on the attached Form PTO/SB/08. No admission is made regarding whether the submitted reference is prior art.

This Supplemental Information Disclosure Statement is being filed with a Request for Continued Examination. Therefore, no fee is believed to be required. However, in the event that a fee is required for filing this Supplemental Information Disclosure Statement, please charge the fee specified under 37 C.F.R. § 1.17(p) to Deposit Account No. 23-0925.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 10/31/08

By: 
Robert C. Hyta
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